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TITLE: METHOD FOR HOLDING PATTERN  
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**ABSTRACT:**

PURPOSE: To provide the industrially advantageous method for holding positive patterns which are excellent in various performances, such as heat

resistance, solvent resistance and adhesion to a base body.

CONSTITUTION: This method for holding the patterns consists in applying a positive type resist compsn. 1 contg. a resin compsn. contg. an alkaline soluble resin and a crosslinking agent, a quinone diazide compd. 2 and a photo-acid generating agent 4 on the base body 5, then exposing the resist compsn. through a mask, developing away the exposed parts to form the positive type resist patterns 6 and curing the resist patterns 6 which are non-exposed patterns or curing these parts by full-surface exposing or curing by an acid after fullsurface exposing.

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